

Contamination control

Building on fifty years of experience in supporting semiconductor development and manufacturing, Eurofins EAG offers a wide range of contamination control services. Through the application of a large number of analytical technologies, we help our customers with contamination control issues as diverse as analysis of supply gases at the ppq levels to sub-monolayer analysis of wafer surfaces. Our services include research and development of new techniques, solving contamination problems on-site and providing routine analyses for existing products and processes.

Leveraging Science and Engineering to Accelerate Innovation

When it comes to understanding the physical structure, chemical properties



and performance of advanced materials and integrated circuitry, no other scientific services company offers the breadth of experience, diversity of analytical techniques or technical ingenuity of Eurofins EAG. We deliver multi-disciplinary, problem-solving expertise to help our customers accelerate innovation, ensure quality and safety, and protect intellectual property.

Cleanroom	Application	Technique
Cleanroom air	Particle count and size	DPC, SEM
	Airborne molecular contamination	GC-FID/MS/AED, IC, ICP-MS, IMS
Supplies: gases	Total organic contamination (TOC)	TD-GC-FID/MS/AED
	Moisture	CRDS, NIR-TDLS, CMS
	Acids/base	IC
	CO/CO ₂	NDIR
	Hydrogen/oxygen	MS, portable monitors
	Particle count and size	DPC, SEM
	Total organic carbon (TOC)	TOC-analyzer
Supplies: ultra-pure water	Anions and cations	IC, ICP-MS
	Particle count and size	LPC
Equipment & Modules		
Cleanliness validation of products & parts	Total organic contamination (TOC)	TD-GC-FID/MS
	Anions and cations	IC, ICP-MS
	Refractory components (S, Si, P, B containing)	GC-MS/AED
	Particle count and size	DPC, LPC, SEM
Outgassing qualifications of materials	Analysis of evolved gases	TD-GC-FID/MS/AED, TGA-MS, TPR-MS
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Trouble shooting	Particles, stains	SEM
	Organics	FT-IR, Raman
	Bulk Impurities	TOF-SIMS, LA-ICP-MS
	Surface contaminants	SEM, XPS, TOF-SIMS, RBS
Wafers & Devices		
Wafers	Particles, stains	SEM, Auger, TEM, AFM
	Organics	FT-IR, Raman, XPS, TOF-SIMS
	Surface contaminants	SEM, XPS, TXRF, TOF-SIMS, VPD-ICP-MS
Devices	Particle etch residue	SEM, XPS, Auger, TEM, AFM
	Organics	FTIR, Raman, XPS, TOF-SIMS
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